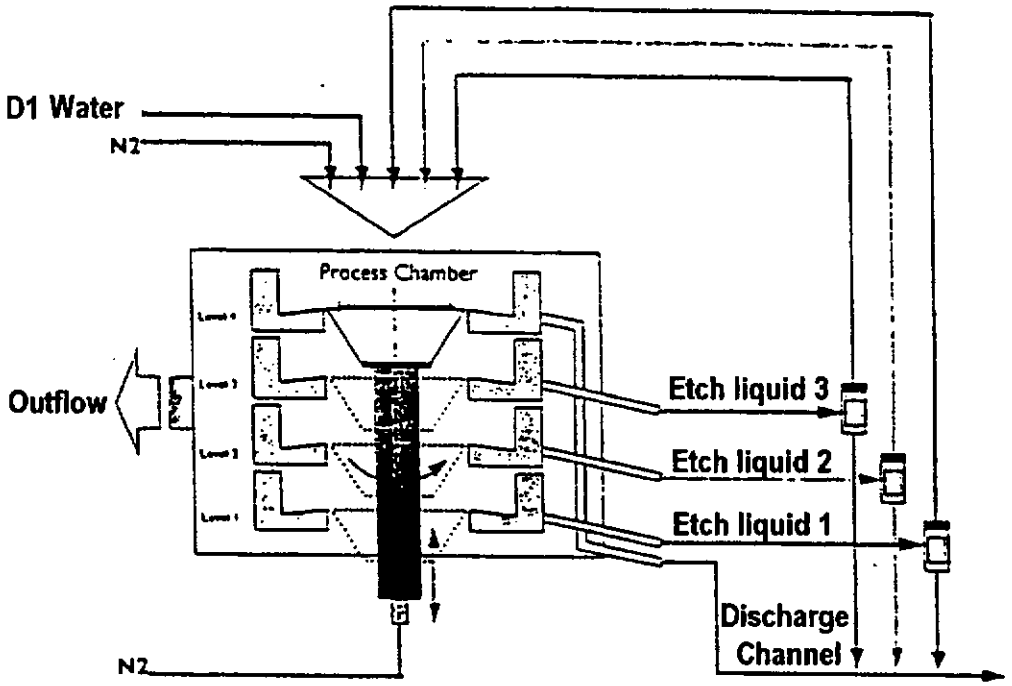
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Fig. 1



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Vertical measurement values

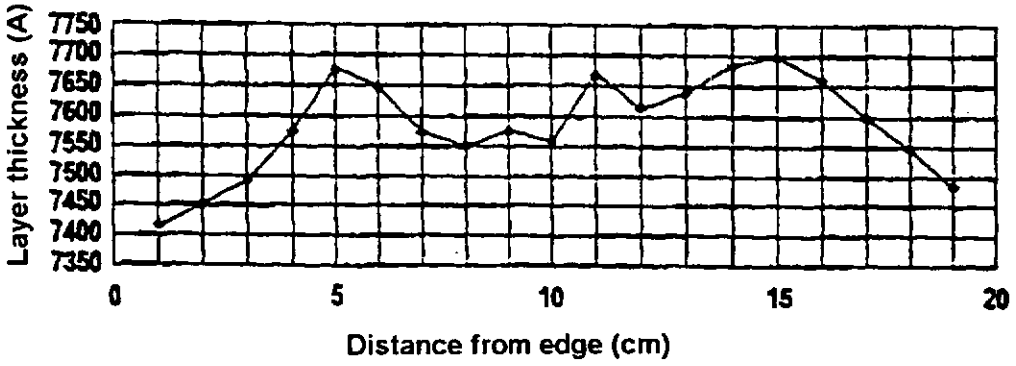
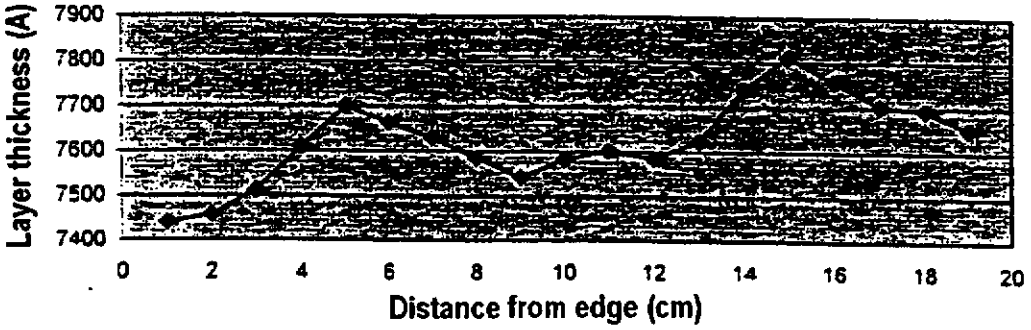


Diagram 2

Horizontal measurement values



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Diagram 3

Wafer profile after etching with ethylene glycol/HF (15%) in a spin etcher

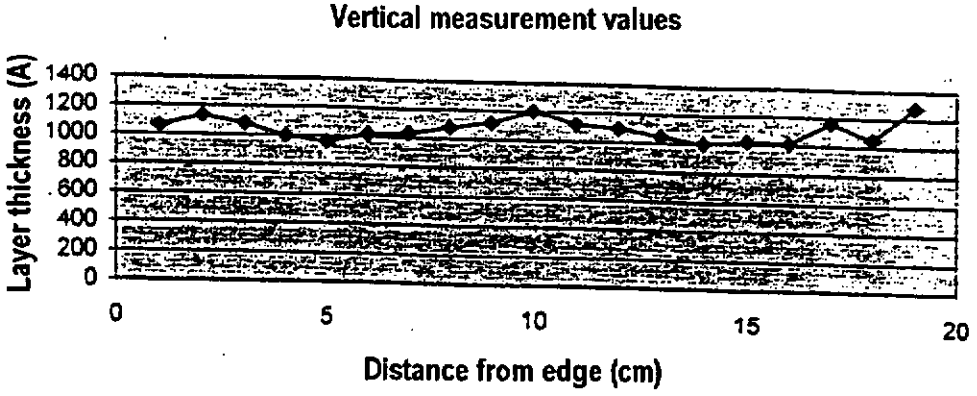
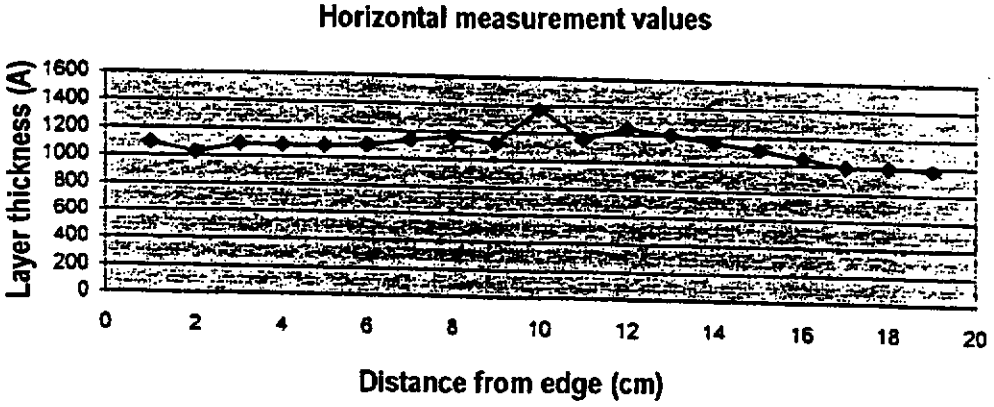


Diagram 4



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Diagram 5

Wafer profile after etching with ethylene glycol/glycerol/HF (15%) in a spin etcher

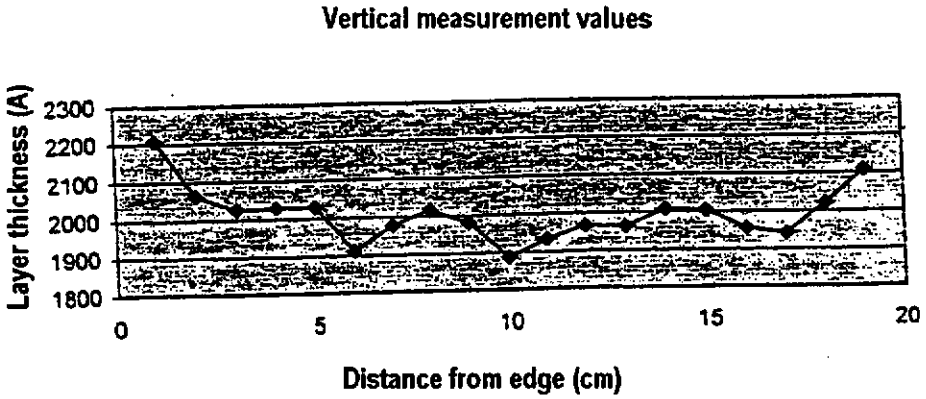


Diagram 6

